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Edited by
M. Hrabovský, M. Konrád, and V. Kopecký

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PREFACE

The 14th International Symposium on Plasma Chemistry has continued the tradition of offering research results in the whole area of plasma chemistry ranging from the basic physics and chemistry of thermal plasmas, low pressure plasmas and high pressure non-equilibrium plasmas to industrial processes, processing techniques and equipment.

These proceedings contain the contributed papers presented at the Symposium and the extended abstracts of invited lectures as well as abstracts of lectures presented at the Workshop on Industrial Applications of Plasma Chemistry. The Workshop was organized as a special session of the Symposium. The full texts of the invited lectures will be published in the following journals: *Pure and Applied Chemistry*, *Plasma Chemistry and Plasma Processing* and *Plasma Sources, Science & Technology*. All the contributed papers were refereed by the International Organizing Committee of ISPC-14 on the basis of one page abstracts to ensure high standard of presented papers.

The proceedings are organized thematically, the papers are grouped into seventeen topics. Papers within each topic are listed in order of their presentation at the Symposium. As the number of papers in individual topics varies considerably the order of presentation of topics in the program of the Symposium could not follow exactly the order of topics in the proceedings. For better orientation the numbers are attached to each paper that indicate the topic and order of presentation in the program.

The high number of papers submitted for presentation at the Symposium reflects continued growth of interest in plasma chemistry science and technology. I believe that these proceedings provide good overview of recent development in this important and interesting field and that they will serve as a useful reference for students, research scientists and engineers at universities, research establishments and industry.

Milan Hrabovský
June 1999